

# Nano Devices, Fabrication and Testing

### **Module Information**

**2022.01, Approved** 

### **Summary Information**

Module Code	7343ELEM
Formal Module Title	Nano Devices, Fabrication and Testing
Owning School	Engineering
Career	Postgraduate Taught
Credits	20
Academic level	FHEQ Level 7
Grading Schema	50

#### **Teaching Responsibility**

LJMU Schools involved in Delivery	
Engineering	

### **Learning Methods**

Learning Method Type	Hours
Lecture	22
Practical	6
Tutorial	11

## Module Offering(s)

Display Name	Location	Start Month	Duration Number Duration Unit
JAN-CTY	CTY	January	12 Weeks

### **Aims and Outcomes**

Aims	To develop an understanding of the state-of-the-art CMOS devices and systems. To gain knowledge in the fabrication and testing of microelectronic devices. To enhance knowledge in latest consumer electronic products.
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#### After completing the module the student should be able to:

#### **Learning Outcomes**

Code	Number	Description
MLO1	1	Show a high level knowledge of the theory and problems of advanced microelectronic devices
MLO2	2	Critically appraise MOS fabrication process and techniques
MLO3	3	Critically evaluate testing techniques and appreciate reliability issues
MLO4	4	Use proprietary industry-standard simulation software for device and fabrication process modelling

### **Module Content**

Outline Syllabus	An overview of the history of microelectronic industry and the milestones in thetheory of microelectronic devicesAdvanced microelectronic devices and systems: submicrometer MOSFETs,FINFETs, non-volatile memories, SOI transistors and thin film transistors (TFTs), andnano-wire devices. Liquid Crystal Display (LCD) systems and Charge-CoupledDevices (CCDs) cameras. Short-channel effects: charge sharing effects, draininduced barrier lowering and gate induced leakage current. New materials formetals, gate dielectrics, and semiconductors.Fabrications: typical MOS process flow and techniques, wafer cleaning, deposition(CVD and PECVD), masks and lithography, ion implantation, metallization, oxidation,epitaxy, dry etching (plasma and reactive ions), isolation techniques, and devicevariabilities.Testing and reliabilities: typical procedure and techniques, time-dependent dielectricbreakdown (TDDB) and stress-induced-leakage-currents (SILC), Fowler-Nordheiminjection, interface states and space charges in the oxide, the high and lowfrequency differential capacitance-voltage techniques, hot carrier induceddegradation, bias temperature instabilities, lifetime prediction.
Module Overview	
Additional Information	This level 7 module extends a prospective student's knowledge of the state-of-the-artelectronic devices and systems. The emphasis is on the differences between anadvanced device and a traditional one. The fabrication, testing and reliability issueswill be addressed.

#### **Assessments**

Assignment Category	Assessment Name	Weight	Exam/Test Length (hours)	Module Learning Outcome Mapping
Centralised Exam	Exam	70	2	MLO1, MLO2, MLO3
Essay	Report	30	0	MLO1, MLO2, MLO4

### **Module Contacts**

#### **Module Leader**

Contact Name	Applies to all offerings	Offerings
Jian Zhang	Yes	N/A

#### Partner Module Team